Correction to: Nano - Precision Systems for Overlay in Advanced Lithography Processes

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Correction to:

**Chapter “Nano - Precision Systems for Overlay in Advanced
Lithography Processes” in: L. Monostori et al. (Eds.):**

***Proceedings of the 4th International Conference on the Industry
4.0 Model for Advanced Manufacturing, LNME,***

https://doi.org/10.1007/978-3-030-18180-2_1

The original version of this chapter starting on page 1 was revised. The incorrect legends of the figures 2, 3, 4, 5, 6 and 7 have been corrected.

The updated version of this chapter can be found at
https://doi.org/10.1007/978-3-030-18180-2_1

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L. Monostori et al. (Eds.): AMP 2019, LNME, p. C1, 2019.

https://doi.org/10.1007/978-3-030-18180-2_18